

[0018] A method for preparing thin supported films by vacuum is disclosed. The method results in a substrate with windows. The windows are cutout (etched) areas that are covered by a thin film. The method for creating the substrate with thin film covering requires: masking off one surface of the metal substrate with a maskant; placing the metal substrate under a vacuum; treating the unmasked surface by plasma etching; coating the treated surface with a film while still under vacuum; removing substrate from vacuum; remove the masking; treating the previously masked side with photo resist; exposing the side treated with photo resist to artwork of a desired pattern; exposing the substrate to a suitable solution; chemically etching in areas selectively exposed by the artwork; neutralizing the substrate; and removing the etched parts from the substrate.